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(71) Applicant: **HITACHI, LTD.**
6, Kanda Surugadai 4-chome Chiyoda-ku
Tokyo 100(JP)

(72) Inventor: **Kikuchi, Hiroshi**
2-8-2, Ikego
Zushi-shi(JP)

(72) Inventor: **Tomizawa, Akira**
Suzuki-Haitsu, 728-1 Shinbashicho
Totsuka-ku Yokohama(JP)

(72) Inventor: **Oka, Hitoshi**
1905-125, Kamariyacho
Kanazawa-ku Yokohama(JP)

(74) Representative: **Altenburg, Udo, Dipl.-Phys. et al,**
Patent- und Rechtsanwälte
Bardehle-Pagenberg-Dost-Altenburg & Partner Postfach
86 06 20
D-8000 München 86(DE)

(54) **Electroless copper plating solution.**

(57) An electroless copper plating solution comprising cupric ions, complexing agents, a reducing agent, a pH adjustor, a polyoxyethylene series surface active agent, these being conventionally used, and (i) an inorganic compound containing at least Si or Ge, or (ii) a cationic surface active agent, or (iii) an inorganic compound containing at least Si, Ge or V and a cationic surface active agent, can give plated films with excellent mechanical properties even if operated for a long period of time with excellent stability of the plating solution.

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ELECTROLESS COPPER PLATING SOLUTION

1

This invention relates to an electroless copper plating solution, and particularly to an electroless copper plating solution which can give an electroless

5 plated copper film with high strength.

In order to give electroless plated copper films with high strength, there is proposed an electroless copper plating solution comprising copper(II) ions, a reducing agent for copper(II) ions, a complexing agent for copper(II) ions, a pH adjustor, α, α' -dipyridyl, poly-
10 ethylene glycol, and an alkali-soluble inorganic silicon compound (Japanese Patent Appln Kokai (Laid-Open) No. 19430/79).

But this electroless copper plating solution
15 uses polyethylene glycol as surface active agent and contains the alkali-soluble inorganic silicon compound in an amount of as low as 5 to 100 mg/l in terms of SiO_2 (0.08 to 1.7 mmole/l in terms of Si atom), so that the
resulting electroless plated copper film is improved in
20 tensile strength and elongation but the stability of the plating solution is not good and there takes place abnormal deposition (a phenomenon of depositing copper on outside of desired portions) when the plating solution is used continuously for a little prolonged time.

1 SUMMARY OF THE INVENTION

It is an object of this invention to provide an electroless copper plating solution excellent in solution stability and capable of forming electroless
5 plated copper films with high mechanical properties.

This invention provides an electroless copper plating solution comprising

- (a) copper ions,
- (b) a copper(II) ion complexing agent,
- 10 (c) a reducing agent,
- (d) a pH adjustor,
- (e) a polyoxyethylene series surface active agent,
- (f) a copper(I) ion complexing agent, and
- (g) (i) an inorganic compound containing at least
15 silicon or germanium, or
- (ii) a cationic surface active agent, or
- (iii) an inorganic compound containing at least silicon, germanium or vanadium and a cationic surface active agent.

20 BRIEF DESCRIPTION OF THE DRAWING

The attached drawing is a graph showing changes of cloud points of a plating solution containing a polyoxyethylene series nonionic surface active agent when various ionic surface active agents are added
25 thereto.

1 DESCRIPTION OF THE PREFERRED EMBODIMENTS

The components (a) to (f) are the same as those used in conventional electroless copper deposition solutions and comprise the following compounds.

5 The copper ions (cupric ions) can be supplied by organic and inorganic cupric salts alone or as a mixture thereof, for example, $\text{CuSO}_4 \cdot 5\text{H}_2\text{O}$, cupric nitrate, cupric chloride, cupric acetate, etc. The concentration of copper(II) ions in the plating solution is usually
10 5 to 50 g/l.

As the copper(II) ion complexing agent, there can be used ethylenediaminetetraacetic acid (EDTA), sodium salts (mono-, di-, tri- and tetrasodium salts) of EDTA, Rochelle salts, hydroxyethylethylenediaminetri-
15 acetic acid (HEDTA), diethylenetriaminepentaacetic acid (DTPA), iminodiacetic acid (IDA), nitrilotriacetic acid (NTA), alkali metal salts (e.g. sodium, potassium, lithium salts) of these acids, alone or as a mixture thereof. When $\text{EDTA} \cdot 2\text{Na}$ is used, it is usually used in
20 an amount of 15 to 200 g/l. When other copper(II) ion complexing agents are used, they are used in a stoichiometrically equal amount to the amount of $\text{EDTA} \cdot 2\text{Na}$.

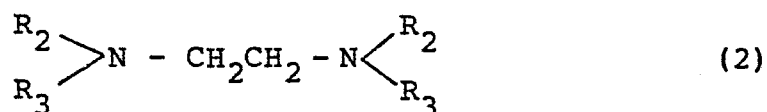
As the reducing agent for copper(II) ions, there can be used formaldehyde, paraformaldehyde,
25 borohydrides, e.g., sodium borohydride, potassium borohydride, hydrazine, etc. When formaldehyde is used, there can preferably be used 2 to 10 ml/l in the form of 37% formaline solution. When other reducing agents

1 are used, they are used in a stoichiometrically equal amount to the amount of formaldehyde.

As the pH adjustor, there can be used alkali metal hydroxides such as sodium hydroxide, potassium hydroxide, etc., alone or as a mixture thereof. The pH adjustor can be used in an amount sufficient to make the pH of plating solution 11 to 13.5.

The polyoxyethylene series surface active agent includes in this invention amine series polyoxyethylene surface active agents (the term "amine series" means "a secondary amine and/or tertiary amine containing") as well as alkyl ester, alkyl ether and acetylene-bond-containing polyoxyethylene surface active agents. Examples of the polyoxyethylene series surface active agents are as follows:

Amine Series Polyoxyethylene Surface Active Agents:

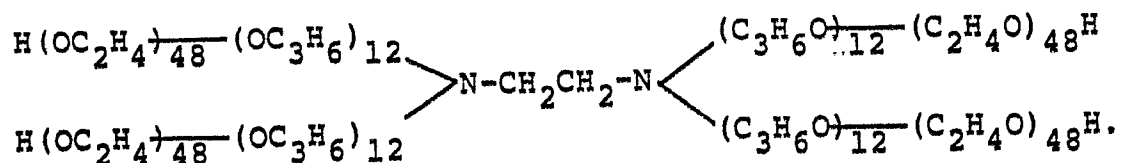


wherein R_1 is an alkyl group preferably having 8 to 18 carbon atoms; R_2 and R_3 are independently a hydrogen atom, a group of the formula: $(CH_2CH_2O)_n-H$, in which n is preferably 5 to 150, a group of the formula:

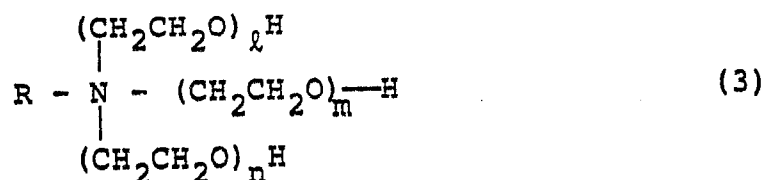
- 5 -

- 1 $-(\text{CH}_2\text{CH}_2\text{O})_m(\text{CH}-\text{CH}_2\text{O})_n\text{H}$, in which m and n are independently preferably 5 to 150.

Among them, preferred ones are polyethylene glycol stearylamine ($n = 15, 20$), and

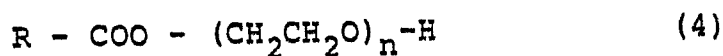


5 Alkylamine Series Polyoxyethylene Surface Active Agents:



wherein R is an alkyl group preferably having 8 to 18 carbon atoms; ℓ , m and n are independently preferably 5 to 150.

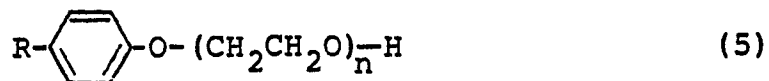
Alkyl Ester Series Polyoxyethylene Surface Active Agents:



- 10 wherein R is an alkyl group preferably having 8 to 18 carbon atoms; n is preferably 5 to 150.

1 Alkyl Aryl Ether Series Polyoxyethylene Surface Active

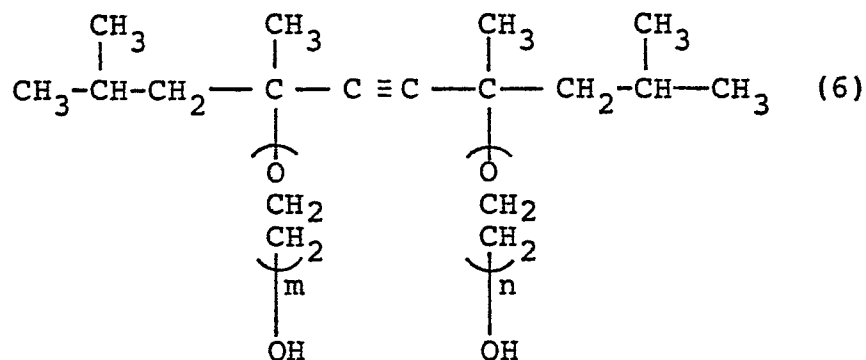
Agents:



wherein R is an alkyl group preferably having 8 to 18 carbon atoms; n is preferably 5 to 150.

5 Acetylene-bond-containing Polyoxyethylene Surface Active

Agents:



wherein m and n are independently preferably 5 to 150.

These polyoxyethylene series surface active agents can be used alone or as a mixture thereof.

- 10 When these surface active agents are used in combination with the component (g) (i) the inorganic compound containing at least silicon or germanium, there can be preferably used amine series polyoxyethylene surface active agents represented by the formulae (1) to
- 15 (3) alone or as a mixture thereof or in combination with one or more other polyoxyethylene surface active agents represented by the formulae (4) to (6).

1 The surface active agent is usually used in
an amount of 0.01 to 2 mmole/l, preferably 0.1 to 1 mmole/l.

As the copper(I) ion complexing agent, there
can be used α, α' -dipyridyl and derivatives thereof, o-
5 phenanthroline and derivatives thereof (e.g., neocuproine),
cuproine, bathocuproine, compounds containing -CN group
such as cyanides (e.g., NaCN, KCN, NiCN, $\text{Co}(\text{CN})_2$,
 $\text{Na}_4[\text{Fe}(\text{CN})_6]$, $\text{K}_4[\text{Fe}(\text{CN})_6]$, $\text{Na}_3[\text{Fe}(\text{CN})_6]$, $\text{K}_3[\text{Fe}(\text{CN})_6]$),
alone or as a mixture thereof. The copper(I) ion
10 complexing agent can be used in an amount of 0.001 to
1 mmole/l usually, and preferably 0.005 to 0.7 mmole/l.

As the component (g), there are three cases (i)
through (iii) depending on purposes.

The case (i) is the use of an inorganic compound
15 containing at least silicon or germanium.

Examples of the inorganic compound containing
at least silicon or germanium is silicon, orthosilicates
such as alkali metal orthosilicates (e.g. sodium
orthosilicate), metasilicates such as alkali metal meta-
20 silicates (e.g. sodium metasilicate), silicon hydride,
etc., germanium, germanium oxide, germanium hydride, etc.
These compounds can be used alone or as a mixture thereof.

The inorganic compound containing at least
silicon or germanium can be used in an amount of 2 mmole/l
25 or more, preferably 2 to 100 mmole/l, more preferably
3 to 30 mmole/l, in terms of silicon or germanium atom.

When the inorganic compound containing at least
silicon or germanium is used, the electroless copper

1 plating solution not only is remarkably improved in
stability without causing abnormal deposition even if
used continuously for a long period of time but also can
form a plated copper film excellent in mechanical pro-
5 perties such as tensile strength and elongation.

The case (ii) is the use of a cationic surface
active agent. There can also be obtained excellent
stability of the plating solution even if used for a long
period of time.

10 Examples of the cationic surface active agent
are quaternary ammonium salts, pyridinium salts, etc.
Among quaternary ammonium salts, tetraalkylammonium salts
and trialkylbenzylammonium salts are preferable. Examples
of tetraalkylammonium salts are hexadecyltrimethylammonium
15 salts, launyltrimethylammonium salt, etc. Examples of
trialkylbenzylammonium salts are stearyltrimethylbenzyl-
ammonium salt, etc. Examples of pyridinium salts are
dodecylpyridinium salt, etc. These cationic surface
active agents can be used alone or as a mixture thereof.

20 The cationic surface active agent can be
used in an amount of preferably 0.02 to 2 mmole/l, more
preferably 0.1 to 1 mmole/l.

In contrast, anionic surface active agents and
amphoteric surface active agents do not give a good
25 effect on the stability of plating solution as shown in
the attached drawing.

The case (iii) is the use of an inorganic
compound containing at least silicon, germanium or

1 vanadium and a cationic surface active agent. As the
inorganic compounds containing at least silicon or
germanium, there can be used those described in the case (i)
above. Examples of the inorganic compound containing at
5 least vanadium are vanadium, vanadium oxide, orthovanadates
such as sodium orthovanadate, metavanadates such as
sodium metavanadate. These inorganic compounds containing
at least silicon, germanium or vanadium can be used alone
or as a mixture thereof.

10 The inorganic compound containing at least
silicon, germanium or vanadium can be used in an amount
of preferably 2 to 100 mmole/l, more preferably 3 to
30 mmole/l in terms of Si, Ge or V atom.

As the cationic surface active agent, there
15 can be used those described in the case (ii) mentioned
above in an amount of preferably 0.02 to 2 mmole/l,
more preferably 0.1 to 1 mmole/l.

By the cause of the inorganic compound contain-
ing at least silicon, germanium or vanadium and the
20 cationic surface active agent, the stability of the plating
solution can be improved more effectively than the
case (i).

This invention is illustrated by way of the
following Examples.

25 Example 1

Electroless copper plating solutions as shown
in Table 1, Nos. 1 to 10 (pH 12.3), were prepared and

1 plating was conducted at 70°C on stainless steel plates.
The plating load factor was made constant at 1 dm²/l.

Each stainless steel plate had been subjected
to instant pyrophosphoric acid electroplating of copper
5 to form plating nucleus, followed by electroless copper
deposition.

With the progress of plating for a long period
of time, since copper(II) ions and other components were
consumed by the plating reaction, concentrations of
10 individual components were detected automatically and
shortage of individual components was supplemented
automatically.

The electroless plating was conducted while
maintaining the concentrations of individual components
15 always constant as mentioned above until the thickness of
deposited metallic copper becomes about 50 μm. Then,
the plated film was peeled off from the stainless steel
plate and subjected to the conventional tensile test.

The results are as shown in Table 1.

Table 1

No.	Composition of electroless copper plating solution*			
	$\text{CuSO}_4 \cdot 5\text{H}_2\text{O}$ (mole/l)	Complexing agent: $\text{EDTA} \cdot 2\text{Na}$ (mole/l)	Formalde- hyde (mole/l)	Copper(I) ion complexing agent (mole/l)
1	0.048	0.096	0.037	α, α' -dipyridyl 1.2×10^{-4}
2	"	"	"	"
3	"	"	"	"
4	0.02	0.04	0.007	Neocuproine 4.8×10^{-6}
5	0.08	0.16	0.037	α, α' -dipyridyl 1.2×10^{-4}
6	0.048	0.096	"	"
7	"	"	"	"
8	"	"	"	"
9	"	"	"	"
10	"	"	"	"

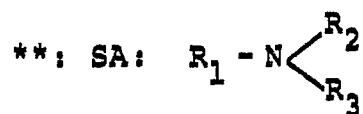
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Table 1 (Cont'd)

Surface active agent** (mole/l)	Si compound (mmole/l) $\text{Na}_2\text{SiO}_3 \cdot 9\text{H}_2\text{O}$	Mechanical properties of plated film		Stability of plating solution after 100 hours' plating
		Tensile strength (Kg/mm ²)	Elongation (%)	
SA-1 2.2×10^{-4}	0	34	8	*** x
"	1	43	6	x
"	3	50	6	o
"	3	51	7	o
"	10	55	6	o
SA-2 2.2×10^{-4}	10	53	6	o
SA-1 2.2×10^{-4}	30	60	5	o
T-707 2.2×10^{-4}	30	62	5	o
SA-1 2.2×10^{-4}	100	67	5	o
"	300	Impossible to measure		-

Notes on Table 1:

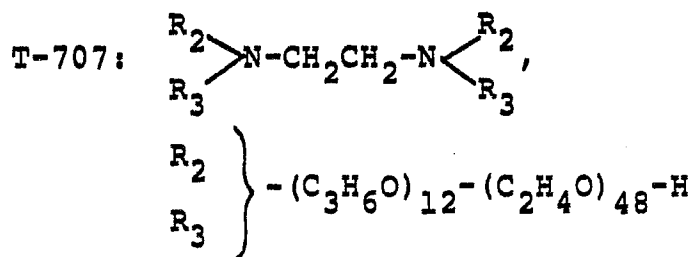
*: pH = 12.3 (by NaOH)



SA-1: $R_1 = C_{18}H_{37}-$, $R_2 = -(C_2H_4O)_{15}H$, $R_3 = H$

SA-2: $R_1 = C_{18}H_{37}-$, $R_2 = -(C_2H_4)_{20}H$

$R_3 = -(C_2H_4)_{20}H$



***: x = no good

o = good

1 In Nos. 3 through 8, the plating rate was
 about 0.5 to 3.0 $\mu\text{m/hr}$ and the plating solutions were
 remarkably stable during the plating. Further, there was
 not admitted a tendency to decompose the plating solutions,
 5 said tendency being inherent to the electroless copper
 plating solution. The resulting plated films of Nos. 3
 to 8 were excellent in gloss of metallic copper as well
 as in mechanical properties. Tensile strength measured
 by using a tensile tester was 50 kg/mm^2 or more and
 10 elongation 4% or more. These properties correspond to
 those (tensile strength 50 - 65 kg/mm^2 , elongation 4 - 6%)

1 of electrodeposited copper films, particularly those
obtained by using a pyrophosphoric acid-copper bath.
Further, the plating solutions of Nos. 3 to 8 were
remarkably stable after continuous 100 hours' operation
5 without causing abnormal deposition.

As is clear from the results in Table 1, the
adding amount (or content) of sodium metasilicate
necessary for giving such excellent properties is 3 to
30 mmole/l in terms of Si atom (85 to 850 mg/l as Si).

10 On the other hand, in the case of No. 10, since
the silicon ions to be adsorbed on the reaction area
are present in excess, the plating reaction was inhibited
to form no plated film. In the case of Nos. 1 and 2
wherein the silicon compound was used in a too small
15 amount or not used, mechanical properties of the plated
films are not good (tensile strength less than 50 kg/mm²,
elongation 6 - 8%) and there took place abnormal deposition
during 100 hours' continuous operation.

As mentioned above, by adjusting the content
20 of Si compound in a suitable amount, mechanical pro-
perties of the resulting plated films can be improved and
the stability of the plating solution can also be
improved.

Further, the use of amine series ethoxy
25 surface active agents are preferable when a Si compound
is used, as shown in Table 1. In addition, a phenanthroline
derivative such as neocuproine (2,9-dimethyl-1,10-
phenanthroline) has the same effect as α, α' -dipyridyl as

1 the copper(I) ion complexing agent.

Example 2

Using electroless copper plating solutions as shown in Table 2, Nos. 11 to 20, electroless copper
5 plating was conducted in the same manner as described in Example 1. Plated films thus obtained had properties as shown in Table 2.

Table 2

No.	Composition of electroless copper plating solution			
	$\text{CuSO}_4 \cdot 5\text{H}_2\text{O}$ (mole/l)	Copper(II) ion complexing agent* (mole/l)	Formal- dehyde (mole/l)	Copper(I) ion complexing agent (mole/l)
11	0.048	EDTA·2Na 0.096	0.037	α, α' -dipyridyl 1.28×10^{-4}
12	"	"	"	"
13	"	"	"	"
14	"	"	"	"
15	"	HEDTA·3Na 0.096	"	"
16	"	"	0.247	1.92×10^{-4}
17	"	DTPA 0.096	0.012	3.20×10^{-5}
18	"	EDTA·2Na 0.096	0.037	o-phenanthroline 6.4×10^{-4}
19	"	"	"	α, α' -dipyridyl 6.4×10^{-4}
20	"	"	"	1.28×10^{-4}

- Cont'd -

Table 2 (Cont'd)

		Mechanical properties of plated film		Stability of plating solution after 100 hours' plating
Surface active agent** (mole/l)	Si compound $\text{Na}_2\text{SiO}_3 \cdot 9\text{H}_2\text{O}$ (mmole/l)	Tensile strength (kg/mm ²)	Elongation (%)	
SA-1 2.2×10^{-4}	0.3	33	8	x
"	1	48	7	x
"	3	54	4	o
"	3	51	6	o
"	3	50	7	o
SA-2 2.2×10^{-4}	10	59	5	o
"	10	50	4	o
EDE-1 2.2×10^{-4}	10	53	5	o
"	30	59	4	o
"	100	65	3	o

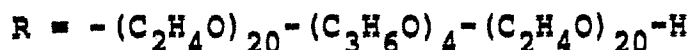
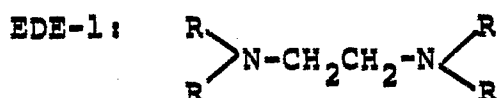
Notes on Table 2:

*: EDTA.2Na = disodium salt of ethylenediamine-tetraacetic acid

HEDTA.3Na = trisodium salt of hydroxyethyl-ethylenediaminetriacetic acid

DTPA = diethylenetriaminepentaacetic acid

** : SA-1, SA-2: see Table 1



1 The plated films obtained in Nos. 13 to 19 had
excellent metallic gloss and high mechanical properties
corresponding to those of electrodeposited copper films.
The content of sodium orthosilicate in Nos. 13 to 19 was
5 3 to 30 mmole/l in terms of Si atom, which values are
the same as in Example 1. Further, the combination of
 α, α' -dipyridyl or phenanthroline or a derivative thereof
and an amine series ethoxy surface active agent was
effective for improving both the elongation and tensile
10 strength. Further, the plating solutions of Nos. 13 to
19 were remarkably stable after continuous 100 hours'
operation without causing abnormal deposition.

Therefore, the electroless copper plating
solutions of Nos. 13 to 19 are suitable for practical use.

15 Example 3

Using electroless copper plating solutions as

- 1 shown in Table 3, Nos. 21 to 24, wherein various Si
compounds which were not dissolved rapidly in the plating
solutions were used in an amount of 10 g/l, electroless
copper plating was conducted in the same manner as
5 described in Example 1. In order to dissolve the Si
compounds, each Si compound was placed in a filter chamber
made of polypropylene and each plating solution heated
at 70°C was recycled through the filter chamber for 5
to 50 hours to dissolve the Si compound.
- 10 Plated films thus obtained had excellent pro-
perties as shown in Table 3. All the plating solutions
were remarkably stable after continuous 100 hours' opera-
tion without causing abnormal deposition.

Table 3

No.	Composition of electroless copper plating solution							Mechanical properties of plated film		Stability of plating solution after 100 hours' plating
	CuSO ₄ ·5H ₂ O (mole/ℓ)	EDTA·2Na (mole/ℓ)	Formaldehyde (mole/ℓ)	α,α'-Dipyridyl (mole/ℓ)	Surface active agent, SA-1 (mole/ℓ)	Si compound (mmole/ℓ) *	Tensile strength (kg/mm ²)	Elongation (%)		
21	0.048	0.096	0.037	1.2x10 ⁻⁴	2.2x10 ⁻⁴	Silica glass powder (5.4)	50	5	o	
22	"	"	"	"	"	Crystalline silica powder (15)	55	4	o	
23	"	"	"	"	"	Silica gel (8.0)	52	4	o	
24	"	"	"	"	"	Silicon powder (3.8)	50	5	o	

Notes) *: The value in parentheses is an analytical value of the amount of Si dissolved in the plating solution.

SA-1: See Table 1.

1 Example 4

Using electroless copper plating solutions as shown in Table 4, Nos. 25 to 29, electroless copper plating was conducted in the same manner as described in Example

5 1.

Plated films obtained by using the plating solution Nos. 26 to 28 had excellent metallic gloss as well as mechanical properties, tensile strength more than 50 kg/mm² and elongation 4% or more.

10 Germanium oxide added to the plating solutions was easily dissolved due to alkalinity to probably give germanate ions such as $[\text{GeO}(\text{OH})_3]^-$, $[\text{GeO}_2(\text{OH})_2]^{2-}$, $\{[\text{Ge}(\text{OH})_4]_8(\text{OH})_3\}^{3-}$, etc. These ions seem to be also effective for improving mechanical properties of plated
15 films and preventing abnormal deposition during a long period of plating like silicate ions.

The most effective concentration of germanium compound in the plating solution is 3 to 30 mmole/l as shown in Table 4 as in the case of Si compounds.

Table 4

No.	Composition of electroless copper plating solution							Mechanical properties of plated film		Stability of plating solution after 100 hours' plating
	CuSO ₄ · 5H ₂ O (mole/l)	EDTA · 2Na (mole/l)	Formaldehyde (mole/l)	α, α'-Dipyridyl (mole/l)	Surface active agent, SA-1 (mole/l)	Ge compound (mmole/l)	Tensile strength (kg/mm ²)	Elongation (%)		
25	0.048	0.096	0.037	1.3x10 ⁻⁴	2.2x10 ⁻⁴	GeO ₂ ₁	48	7	x	
26	"	"	"	"	"	3	51	5	o	
27	"	"	"	"	"	10	55	6	o	
28	"	"	"	"	"	30	60	4	o	
29	"	"	"	"	"	100	67	2	o	

Notes) SA-1: See Table 1.

1 Example 5

Using electroless copper plating solutions as shown in Table 5, Nos. 30 to 33, electroless copper plating was conducted in the same manner as described in Example

- 5 1. As shown in Table 5, various copper(I) ion complexing agents, surface active agents and Si or Ge compounds alone or in combination were used.

The resulting plated films had properties as shown in Table 5. As is clear from Table 5, the plated
10 films had the same excellent tensile strength, elongation and the plating solution stability as those obtained when individual components are used alone.

Table 5

No.	Composition of electroless copper plating solution					
	$\text{CuSO}_4 \cdot 5\text{H}_2\text{O}$ (mole/l)	EDTA-2Na (mole/l)	Formaldehyde (mole/l)	Copper(I) ion complexing agent (mole/l)	Surface active agent (mole/l)	Si, Ge compound (mmole/l)
30	0.05	0.12	0.054	α, α' -Dipyridyl 1.3×10^{-4} o-Phenanthroline 5×10^{-6}	SA-1 2.2×10^{-4}	$\text{Na}_2\text{SiO}_3 \cdot 9\text{H}_2\text{O}$ 3
31	"	"	"	α, α' -Dipyridyl 1.3×10^{-4}	SA-1 2.2×10^{-4} SA-2 2.2×10^{-4}	"
32	"	"	"	"	SA-1 2.2×10^{-4}	$\text{Na}_2\text{SiO}_3 \cdot 9\text{H}_2\text{O}$ 3 GeO_2 6
33	"	"	"	α, α' -Dipyridyl 1.3×10^{-4} o-Phenanthroline 5×10^{-6}	SA-1 2.2×10^{-4} SA-2 2.2×10^{-4}	"

Notes) SA-1, SA-2: See Table 1.

- Cont'd -

Table 5 (Cont'd)

Mechanical properties of plated film		Stability of plating solution after 100 hours' plating
Tensile strength (kg/mm ²)	Elongation (%)	
53	4	0
53	6	0
55	5	0
51	6	0

1 Example 6

Using electroless copper plating solutions as shown in Table 6, Nos. 34 to 41, electroless copper plating was conducted in the same manner as described in Example 1. In Nos. 34 to 41, combinations of surface active agents A to D and Si or Ge compound were changed. The plating rate was about 0.5 to 3.0 $\mu\text{m/hr}$ in Nos. 34 to 41 and the plating solutions were remarkably stable during the plating. Further, there was not admitted a tendency to decompose the plating solutions, said tendency being inherent to the electroless copper plating solution.

The resulting plated films of Nos. 34 to 41 were excellent in metallic copper gloss as well as in mechanical properties. Tensile strength was 50 kg/mm^2 or more and elongation 4% or more.

Table 6

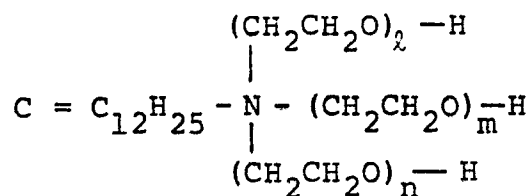
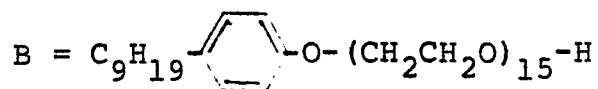
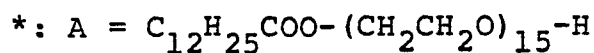
Composition of electroless copper plating solution							
No.	$\text{CuSO}_4 \cdot 5\text{H}_2\text{O}$ (mole/l)	EDTA·2Na (mole/l)	Formaldehyde (mole/l)	α, α' -Dipyridyl (mole/l)	Surface active agent* (mole/l)	Si, Ge compound (mmole/l)	
34	0.04	0.12	0.04	1.9×10^{-4}	A 1.1×10^{-4}	$\text{Na}_2\text{SiO}_3 \cdot 9\text{H}_2\text{O}$ 10	
35	"	"	"	"	B 1.1×10^{-4}	"	
36	"	"	"	"	C 2.0×10^{-4}	"	
37	"	"	"	"	D 6.7×10^{-5}	"	
38	"	"	"	"	A 1.1×10^{-4}	GeO_2 10	
39	"	"	"	"	B 1.1×10^{-4}	"	
40	"	"	"	"	C 2.0×10^{-4}	"	
41	"	"	"	"	D 6.7×10^{-5}	"	

- Cont'd -

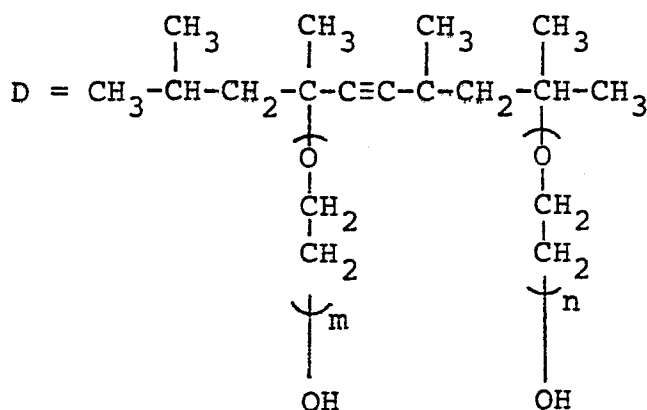
Table 6 (Cont'd)

Mechanical properties of plated film		Stability of plating solution after 100 hours' plating
Tensile strength (kg/mm ²)	Elongation (%)	
54	6	0
56	4	0
53	5	0
51	7	0
55	5	0
55	6	0
50	8	0
52	5	0

Notes on Table 6:



$$(\ell + m + n = 7)$$



$$(m + n = 30)$$

1 Comparative Example 1

Using electroless copper plating solutions as shown in Table 7, Nos. 42 to 46, electroless copper plating was conducted in the same manner as described in Example 1.

5 In Nos. 42 to 45, although sodium metasilicate was contained in amounts of 3 to 10 mmole/l, surface active agents used were not suitable for this invention. No. 46 did not contain Si compound.

The results were as shown in Table 7.

10 When the surface active agents are different from those usable in this invention as shown in Nos. 42

1 and 43, the elongation of the plated films is poor. When
a phosphoric acid ester series surface active agent
is used as in No. 44, the plating reaction is stopped,
although said surface active agent contains a poly-
5 oxyethylene group. The stoppage of plating reaction
seems to be the excess adsorption force of the added
component. When SH-192 was used as surface active agent
as in No. 45, no effect of this invention was exhibited.
Further, when no Si compound was added as in No. 46,
10 mechanical properties were not improved at all.

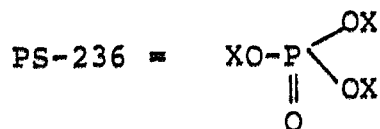
Table 7

No.	Composition of electroless copper plating solution						Mechanical properties of plated film	
	CuSO ₄ ·5H ₂ O (mole/l)	EDTA·2Na (mole/l)	Formal- dehyde (mole/l)	Copper(I) ion complexing agent (mole/l)	Surface active agent*	Si compound (mmole/l)	Tensile strength (kg/mm ²)	Elonga- tion (%)
42	0.048	0.096	0.037	α,α'-Dipyridyl 1.3 x 10 ⁻⁴	POE 2.2x10 ⁻⁴	Na ₂ SiO ₃ ·9H ₂ O 5	55	1
43	"	"	"	"	SE 2.2x10 ⁻⁴	3	58	1
44	"	"	"	o-Phenanthro- line 6.4 x 10 ⁻⁴	PS-236 200 mg/l	10	Impossible to measure	
45	"	"	"	"	SH-192 200 mg/l	10	57	2
46	"	"	"	α,α'-Dipyridyl 2.2 x 10 ⁻³	SA-1 2.2 x 10 ⁻⁴	0	32	8

Notes on Table 7:

*: POE = polyethylene glycol (mol. wt. 600)

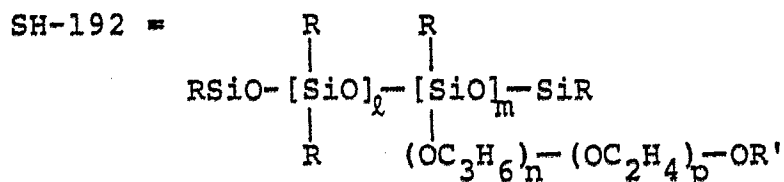
SE = polyoxyethylene stearyl ether



X = $-(\text{OC}_2\text{H}_4)_n-$ OR or H

R = an alkyl group

n = an integer



R = a methyl group

R' = an alkyl group or H

ℓ, m, n, p = integers

1 Comparative Example 2

Using electroless copper plating solutions as shown in Table 8, Nos. 47 to 49, electroless copper plating was conducted in the same manner as described in

5 Example 1.

The results were shown in Table 8.

When no Si or Ge compound is used as in No. 47, the plated film is poor in mechanical properties. When no surface active agent is used as in No. 48, the
10 stability of the plating solution is insufficient even if a Si compound is contained, so that the plating solution is decomposed and no plated film is obtained. When both

- 1 a surface active agent and a Si or Ge compound are not contained in the plating solution as in No. 49, the degree of decomposition of the plating solution becomes greater.

Table 8

No.	Composition of electroless copper plating solution						Mechanical properties of plated film	
	$\text{CuSO}_4 \cdot 5\text{H}_2\text{O}$ (mole/l)	EDTA · 2Na (mole/l)	Formal- dehyde (mole/l)	α, α' - Dipyridyl (mole/l)	Surface active agent* (mole/l)	Si compound (mmole/l)	Tensile strength (kg/mm ²)	Elongation (%)
47	0.04	0.12	0.04	1.9×10^{-4}	1.1×10^{-4}	-	33	8
48	"	"	"	"	"	$\text{Na}_2\text{SiO}_3 \cdot 9\text{H}_2\text{O}$ 10	Impossible to measure	
49	"	"	"	"	-	-	Impossible to measure	

1 Example 7

To an electroless copper plating solution comprising:

CuSO ₄ ·5H ₂ O	10 g
EDTA·2Na	30 g
NaOH	a sufficient amount to make the pH 12.2
37% formaldehyde solution	3 ml
α,α'-dipyridyl	3.2 x 10 ⁻⁴ mole
polyoxyethylene series nonionic surface active agent	1.1 x 10 ⁻⁴ mole
Water	an amount to make the solution 1 liter

sodium sulfate and sodium formate as build-up component
 5 in the plating solution were added in various concentrations to measure changes of cloud points of the plating solution. As the polyoxyethylene series nonionic surface active agent, polyethylene glycol stearylamine was used. The temperature at which polyethylene glycol
 10 stearylamine agglomerates was defined as a cloud point of plating solution. The cloud points of the plating solutions were measured and listed in Table 9.

Table 9

Concentration of anions (g/l)		Cloud point of plating solution (°C)
Na ₂ SO ₄	HCOONa	
7.0	0	90
14.0	6.8	85
21.0	13.6	79
28.0	20.4	75
36.0	27.2	69
45.0	34.0	65

1 As is clear from Table 9, the cloud point decreases linearly with an increase of adding amounts of sodium sulfate and sodium formate.

Next, the effect of various inonic surface
 5 active agents on the increase of cloud point of plating solution was examined by using the above-mentioned plating solution further containing 28.0 g/l of sodium sulfate (SO₄²⁻ concentration in the plating solution: 112 g/l) and 20.4 g/l of sodium formate (HCOO⁻ concentration in
 10 the plating solution: 102 g/l). The results are shown in the attached drawing. As is clear from the drawing, the effect of increasing the cloud point of plating solution is most remarkable in the case of cationic surface active agents (the curve A = cetyltrimethylammonium
 15 chloride, the curve B = dodecylpyridinium chloride), next effective in the case of amphoteric surface active

1 agents (the curve D = stearyl betaine), and slightly
effective in the case of anionic surface active agents
(the curve C = dodecylbenzene sulfonate, the curve E =
sulfosuccinic acid ester, the curve F = sodium polyoxy-
5 ethylene laurylsulfate).

In the next place, influences of various poly-
oxyethylene series nonionic surface active agents on
the increasing effect of cetyltrimethylammonium chloride
on the cloud point were examined by using the above-
10 mentioned plating solution further containing 50 mg/l of
cetyltrimethylammonium chloride, 28.0 g/l of sodium
sulfate and 20.4 g/l of sodium formate.

The results are shown in Table 10.

Table 10

Polyoxyethylene series nonionic surface active agent	Cloud point (°C)	
	No addition	Added
TETORONICS 704	60	95
TETORONICS 707	95	>100
PLURONICS L64	52	87
PLURONICS P85	79	>100
Polyoxyethylene octylphenol ether	58	92
Polyoxyethylene lauryl ether	69	>100

Notes on Table 10:

TETRONICS	}	-	Polyoxyethylene-polyoxypropylene block polymer manufactured by Asahi Denka Kogyo K.K.
PLURONICS			

- 1 As is clear from Table 10, the cloud point is increased in all the cases irrespective of the kinds of polyoxyethylene series nonionic surface active agents.

Example 8

- 5 An electroless copper plating solution was prepared by adding 50 mg of cetyltrimethylammonium chloride to 1 liter of the following composition:

CuSO ₄ ·5H ₂ O	10 g
EDTA·2Na	30 g
NaOH	a sufficient amount to make the pH 12.2
α,α'-dipyridyl	40 mg
37% formaldehyde solution	3 ml
polyethylene glycol stearylamine	100 mg
water	an amount to make the solution 1 liter

- 10 Electroless copper plating was conducted in the same manner as described in Example 1. Even when the total plating time reached 100 hours, foaming properties of the plating solution was still admitted (the effect of the surface active agent remaining) and no abnormal deposition (copper deposition on outside the

1 desired portion of an insulating material) was not admitted.
ted.

The resulting plated film at the initial stage
had excellent mechanical properties, i.e., tensile
5 strength of 52 kg/mm² and elongation of 6%.

Example 9

CuSO ₄ ·5H ₂ O	10 g
EDTA·2Na	30 g
NaOH	a sufficient amount to make the pH 12.1
37% formaldehyde solution	3 ml
o-phenanthroline	1 mg
polyoxyethylene laurylamine	200 mg
laurylbenzyltrimethyl- ammonium chloride	50 mg
water	an amount to make the solution 1 liter

Using the above-mentioned electroless copper
plating solution, electroless copper plating was conducted
for 120 hours in the same manner as described in Example 1,
10 but no abnormal deposition was admitted.

The resulting plated film at the initial stage
had excellent mechanical properties, i.e., tensile
strength of 55 kg/mm² and elongation of 4%.

Example 10

CuSO ₄ ·5H ₂ O	15 g
--------------------------------------	------

EDTA·2Na	45 g
NaOH	a sufficient amount to make the pH 12.3
37% formaldehyde solution	3 ml
α, α' -dipyridyl	1.9×10^{-4} mole
polyethylene glycol stearylamine (n=15)	1.1×10^{-4} mole
cetyltrimethylammonium chloride	1.4×10^{-4} mole
laurylbenzyltrimethylammonium chloride	2.0×10^{-4} mole
water	an amount to make the solution 1 liter

- 1 Using the above-mentioned electroless copper plating solution, electroless copper plating was conducted for 120 hours in the same manner as described in Example 1, but no abnormal deposition was admitted, since a
- 5 mixture of two kinds of cationic surface active agents were used.

The resulting plated film had excellent mechanical properties, i.e., tensile strength of 52 kg/mm² and elongation of 5%.

10 Example 11

CuSO ₄ ·5H ₂ O	15 g
EDTA·2Na	45 g
NaOH	a sufficient amount to make the pH 12.3
37% formaldehyde solution	3 ml

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α, α' -dipyridyl	1.9×10^{-4} mole
polyethylene glycol stearylamine (n=15)	1.1×10^{-4} mole
polyoxyethylene laurylamine (n=20)	9.4×10^{-5} mole
cetyltrimethylammonium chloride	1.4×10^{-4} mole
water	an amount to make the solution 1 liter

- 1 Using the above-mentioned electroless copper plating solution, electroless copper plating was conducted for 120 hours in the same manner as described in Example 1, but no abnormal deposition was admitted, since two
- 5 kinds of nonionic polyoxyethylene surface active agents and a cationic surface active agent were co-used.

The resulting plated film had excellent mechanical properties, i.e., tensile strength of 55 kg/mm² and elongation of 5%.

10 Example 12

[I] Composition of electroless copper plating solution

$\text{CuSO}_4 \cdot 5\text{H}_2\text{O}$	0.048 mole
EDTA·2Na	0.11 mole
NaOH	a sufficient amount to make the pH 12.2
37% formaldehyde solution	4 ml
α, α' -dipyridyl	3.5×10^{-4} mole
polyethylene glycol stearylamine	1.1×10^{-4} mole

sodium metasilicate	3.5×10^{-3} mole
water	an amount to make the solution 1 liter

1 [II] Conditions of plating

- (i) plating temperature: 70°C
- (ii) plating load factor: $100 \text{ cm}^2/\ell$
- (iii) volume of plating tank: 50 liters

5 [III] Experimental method

In order to know influences of substances dissolved into the plating solution from a substrate for printed wiring board, a substrate made from an epoxy resin (thickness 1.6 mm, no copper foil on both sides) was used.

10 A stainless steel plate and the epoxy resin substrate were dipped in the plating solution at $100 \text{ cm}^2/\ell$ and electroless copper plating was conducted on the stainless steel plate, while dissolution of the epoxy resin substrate into the plating solution was carried
15 out at the same time.

After plating to the thickness of $35 \mu\text{m}$, the plated film was peeled off from the stainless steel plate and cut into a size of $1 \times 10 \text{ cm}$. Mechanical properties of the plated film were measured by using a
20 tensile tester by a conventional method.

The number of plating means the number of repeating so as to make the thickness $35 \mu\text{m}$ at the plating load factor of $100 \text{ cm}^2/\ell$.

With the progress of plating, the concentrations

- 1 of plating reaction components in the plating solution were decreased. But the concentrations of these components were always maintained constant by means of automatic analysis of these concentrations and automatic
- 5 supplement of consumed components.

Tensile strength of resulting plated film was measured and listed in Table 11-1.

Table 11-1

No. of plating	1	2	4	5
Tensile strength (kg/mm ²)	42	26	20	Plating was stopped

- Since substances dissolved from the epoxy resin substrate made the plating solution unstable and the
- 10 tensile strength of the resulting plated films was lowered as shown in Table 11-1, the electroless plating was stopped at the fifth plating.

On the other hand, when the following cationic surface active agent, i.e.

hexadecyltrimethylammonium bromide: 1.4×10^{-4} mole/l
 $[C_{16}H_{33}N(CH_3)_3]Br$

- 15 was added to the same electroless copper plating solution as mentioned above, electroless copper plating was able to be repeated 10 times (about 150 hours) even if the epoxy resin substrate was dipped in the plating solution.

1 The results are shown in Table 11-2.

Table 11-2

No. of plating	1	2	4	6	8	10
Tensile strength (kg/mm ²)	61	60	58	55	55	56
Elongation (%)	4	5	6	7	7	6

As is clear from Table 11-2, the plated film obtained at the first plating had tensile strength of 61 kg/mm² and elongation of 4% as well as mirror-like
5 gloss. It is a very surprising thing that no deposition on the walls of the plating tank took place even after 10 times plating (about 150 hours' plating).

This clearly means that the cationic surface active agent is effective for preventing the plating
10 solution from the influences of substances dissolved out of the epoxy resin substrate.

The same effect as mentioned above was identified when a plating tank having a volume of 5000 liters was used. That is, even after repeating the electroless
15 copper plating 10 times, the resulting plated film had excellent mechanical properties, i.e., tensile strength of 56 kg/mm² and elongation of 6%.

Example 13

The process of Example 12 using the cationic

1 surface active agent was repeated except for using Si, Ge or V compound in amounts as listed in Table 12.

The results are as shown in Table 12.

As is clear from Table 12, excellent results
5 are obtained in the portions marked with o.

Table 12

Si, Ge, or V compound	Adding amount (mmole/l in terms of Si, Ge or V atom.)									
	0.0006	0.001	0.01	1	3	10	30	50	100	200
$\text{Na}_2\text{SiO}_3 \cdot 9\text{H}_2\text{O}$	x	x	x	o	o	o	o	o	x	x
Na_2SiO_4	x	x	x	x	o	o	o	o	x	x
GeO_2	x	x	x	x	o	o	o	x	x	x
V_2O_5	x	x	x	o	o	o	o	x	x	x
$\text{VOSO}_4 \cdot 2\text{H}_2\text{O}$	x	x	x	o	o	o	o	x	x	x

Notes) o: Plated film had tensile strength of 50 kg/mm² or more and elongation of 4% or more, and no abnormal deposition took place even after continuous 100 hours' plating.

x: Either plated film had tensile strength of less than 50 kg/mm² and elongation of less than 4%, or abnormal deposition took place after continuous 100 hours' plating.

Example 14

The process of Example 12 using the cationic surface active agent was repeated except for using cationic surface active agents as listed in Table 13 in
10 place of hexadecyltrimethylammonium bromide.

1 The results are as shown in Table 13.

As is clear from Table 13, excellent results are obtained in the portions marked with o.

Table 13

Cationic surface active agent	Adding amount (mmole/l)					
	0.01	0.02	0.1	1	2	5
Hexadecyltrimethylammonium bromide $[C_{16}H_{33}N(CH_3)_3]Br$	x	o	o	o	o	x
Stearyl dimethylbenzylammonium chloride $[C_{17}H_{35}-N(CH_3)_2-CH_2-C_6H_5]Cl$	x	o	o	o	o	x
Dodecylpyridinium chloride $[C_{12}H_{25}-N(C_5H_5)]Cl$	x	o	o	o	o	x

Notes) o, x: See Table 12.

Example 15

5 The process of Example 12 using the cationic surface active agent was repeated except for using polyoxyethylene series nonionic surface active agents as listed in Table 14 were used in place of polyethylene glycol stearylamine.

10 The results are as shown in Table 14.

- 1 As is clear from Table 14, excellent results are obtained in the portions marked with o.

Table 14

Polyoxyethylene nonionic surface active agent	Adding amount (mmole/l)						
	5×10^{-3}	0.01	0.05	0.1	1	2	5
$C_{18}H_{37}-NH-(C_2H_4O)_{15}-H$	x	o	o	o	o	o	x
$C_{18}H_{37}-N^+(C_2H_4O)_{10}-H]_2$	x	o	o	o	o	x	x

Notes) o, x: See Table 12.

Comparative Example 3

- 5 Using the following electroless copper plating solution, electroless copper plating was conducted in the same manner as described in Example 12.

$CuSO_4 \cdot 5H_2O$	15 g
EDTA · 2Na	45 g
37% formaldehyde solution	3 ml
NaOH	a sufficient amount to make the pH 12.1
α, α' -dipyridyl	1.9×10^{-4} mole
polyethylene glycol (mol. wt. 600)	1.7×10^{-4} mole
sodium metasilicate	1.0×10^{-4} mole
water	an amount to make the solution 1 liter

Abnormal deposition took place after about

- 1 50 hours' continuous plating; that is, the stability of the plating solution was not good.

C L A I M S

1. An electroless copper plating solution comprising:
 - (a) copper ions,
 - (b) a copper(II) ion complexing agent,
 - (c) a reducing agent,
 - (d) a pH adjustor,
 - (e) a polyoxyethylene series surface active agent,
 - (f) a copper(I) ion complexing agent, and
 - (g) (i) an inorganic compound containing at least silicon or germanium, or
(ii) a cationic surface active agent, or
(iii) an inorganic compound containing at least silicon, germanium or vanadium and a cationic surface active agent.
2. An electroless copper plating solution according to Claim 1, wherein the component (g) is
 - (i) an inorganic compound containing at least silicon or germanium in an amount of 2 mmole/l or more in terms of silicon or germanium atom.
3. An electroless copper plating solution according to Claim 1, wherein the component (g) is
 - (ii) a cationic surface active agent.
4. An electroless copper plating solution according to Claim 1, wherein the component (g) is
 - (iii) an inorganic compound containing at least silicon, germanium or vanadium in an amount of 2 mmole/l or more in terms of silicon, germanium or vanadium atom

and a cation surface active agent.

5. An electroless copper plating solution according to Claim 2, wherein the inorganic compound containing at least silicon or germanium is used in an amount of 3 to 30 mmole/l in terms of silicon or germanium atom.

6. An electroless copper plating solution according to Claim 2, wherein the inorganic compound containing at least silicon or germanium is at least one member selected from the group consisting of silicon, ortho-silicates, metasilicates, silicon hydride, germanium, germanium oxide and germanium hydride.

7. An electroless copper plating solution according to Claim 3, wherein the cationic surface active agent is used in an amount of 0.02 to 2 mmole/l.

8. An electroless copper plating solution according to Claim 3, wherein the cationic surface active agent is at least one member selected from the group consisting of quaternary ammonium salts and pyridinium salts.

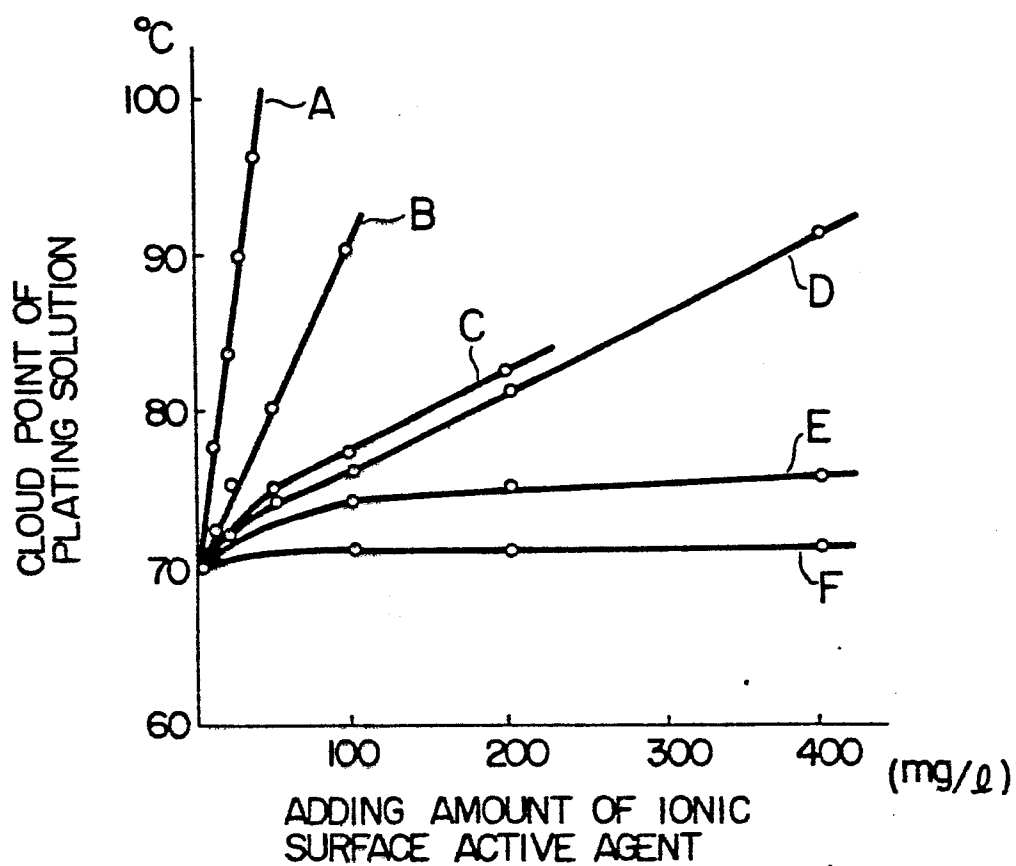
9. An electroless copper plating solution according to Claim 4, wherein the inorganic compound containing at least silicon, germanium or vanadium is used in an amount of 2 to 100 mmole/l in terms of silicon, germanium or vanadium atom and the cationic surface active agent is used in an amount of 0.02 to 2 mmole/l.

10. An electroless copper plating solution according to Claim 4, wherein the inorganic compound containing at least silicon, germanium or vanadium is at least one member selected from the group consisting of silicon,

orthosilicates, metasilicates, silicon hydride, germanium, germanium oxide, germanium hydride, vanadium, vanadium oxide, and metavanadates, and the cation surface active agent is at least one member selected from the group consisting of quaternary ammonium salts and pyridinium salts.

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DOCUMENTS CONSIDERED TO BE RELEVANT			EP 84107191.3
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl. 4)
D,Y	PATENT ABSTRACTS OF JAPAN, unexamined applications, C section, vol. 3, no. 43, April 13, 1979 THE PATENT OFFICE JAPANESE GOVERNMENT page 163 C 42 * Kokai-no. 54-19 430 (HITACHI SEISAKUSHO K.K.) * --	1,4,6,10	C 23 C 18/40
Y	EP - A1 - 0 039 757 (TOKYO SHIBAURA DENKI KABUSHIKI KAISHA) * Abstract; claim 1 * --	1	
Y	GB - A - 1 161 550 (THE PYRENE COMPANY LIMITED) * Page 4, lines 8-13; claims * --	1,3,7,8,10	
Y	GB - A - 1 352 087 (SHIPLEY COMPANY INC.) * Examples; claims * --	1	TECHNICAL FIELDS SEARCHED (Int. Cl. 4) C 23 C
Y	GB - A - 1 330 332 (PHILIPS ELECTRONIC AND ASSOCIATED INDUSTRIES LIMITED) * Claims * --	1,4,10	
Y	GB - A - 1 126 327 (PHOTOCIRCUITS CORPORATION) * Table 1; claims * --	1,4,10	
The present search report has been drawn up for all claims			
Place of search VIENNA		Date of completion of the search 24-09-1984	Examiner SLAMA
CATEGORY OF CITED DOCUMENTS X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document			



EUROPEAN SEARCH REPORT

01 32594

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EP 84107191.3

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